molecules

MDPI

SUPPORTING INFORMATION

Crystallization of Polytetrafluoroethylene in a Wide Range of Cooling Rates: Nucleation and Diffusion in the Presence of Nanosilica Clusters

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1. Transmission Electron Microscopy

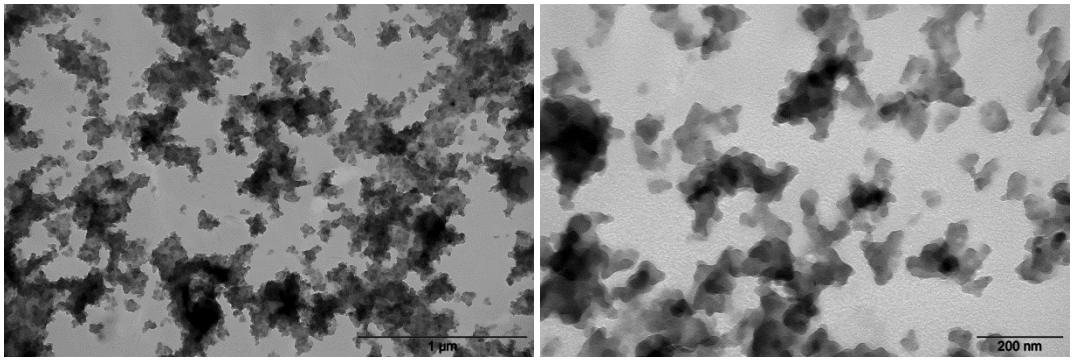
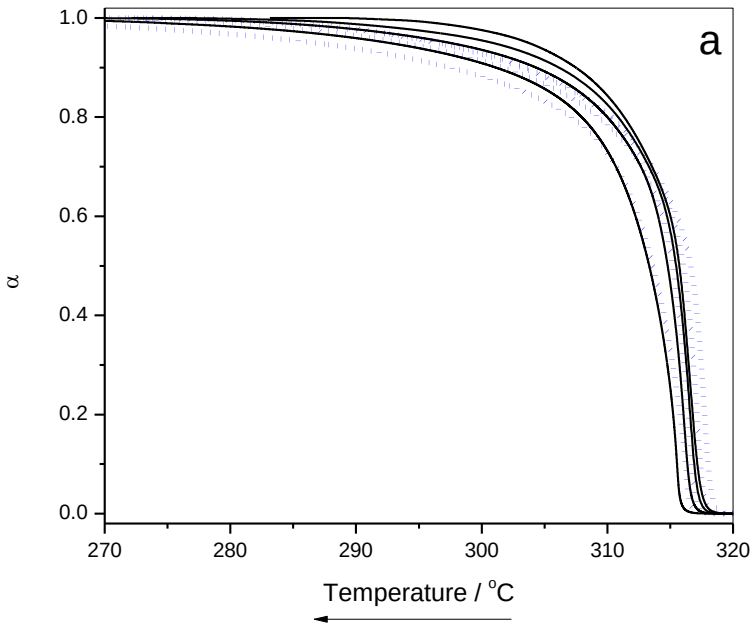
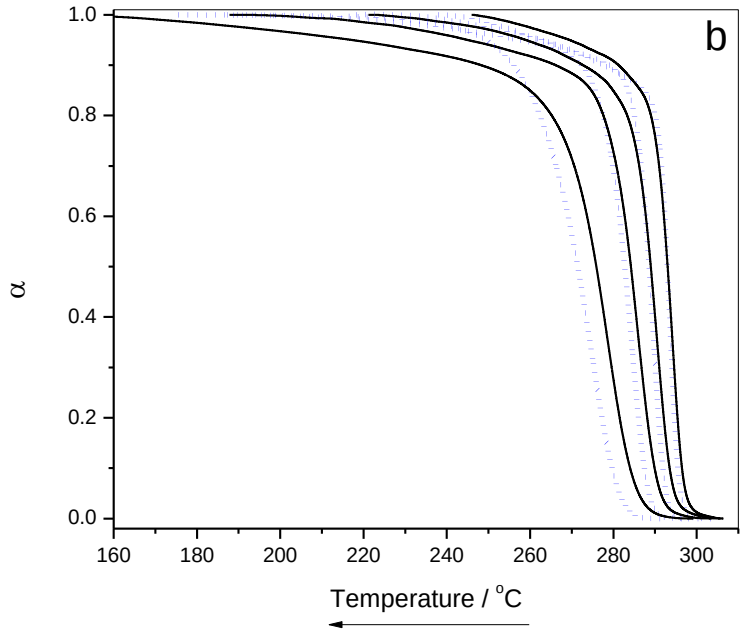


Figure 1. TEM pictures of SiO_2(c) nanoparticles.

2. Relative Degree of Crystallinity Versus Temperature



(a)



(b)

Figure 2. Relative degree of crystallinity vs temperature during the nonisothermal crystallization from the melt of neat PTFE (black, line) and PTFE/ SiO_2(c)F (blue, dot) obtained by DSC (**a**) and FSC (**b**). The cooling rate of each experiment (in $K \cdot s^{-1}$) is indicated by each curve. Inset: magnification of the α vs T curve at the beginning of crystallization process.